

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Satoshi TAKEI et al.

Application No.: 10/540,389

Filed: July 20, 2005

Docket No.: 124418

For: ALKALI-SOLUBLE GAP FILLING MATERIAL FORMING COMPOSITION FOR
LITHOGRAPHY

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450


Sir:

Pursuant to 37 CFR §1.56, the attention of the Patent and Trademark Office is hereby directed to the references listed on the attached PTO-1449. Unless otherwise indicated herein, one copy of each reference is attached. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the references be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

- ☒ 1. This Information Disclosure Statement is being filed (a) within three months of the U.S. filing date of this non-CPA application, OR (b) before the mailing date of a first Office Action on the merits in the present application. No certification or fee is required.
- ☒ 2. Relevance of references 2-5 and 8-14 is discussed in the present specification.
- ☒ 3. The references 1 and 5-7 were cited in the International Search Report. An English language version of the International Search Report is attached for the Examiner's information.
- ☒ 4. In accordance with 37 CFR §1.98(a)(2)(ii), copies of any U.S. patents and patent application publications are not attached.
- ☒ 5. English language Abstracts of the non-English language references 5, 7, 8, 10 and 11 are attached hereto.

- ☒ 6. A computer-generated English language translation of the following Japanese Patent Publication has been obtained from the website of the Japanese Patent Office (<http://www.jpo.go.jp>), and is attached, but has not been reviewed for accuracy. See References 7, 8 and 11.

Respectfully submitted,



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AUTHORIZATION

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Form PTO-1449 (REV. 8-83)		US Dept. of Commerce PATENT & TRADEMARK OFFICE		ATTY DOCKET NO. 124418		APPLICATION NO. 10/540,389	
INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary)				APPLICANTS Satoshi TAKEI et al.			
				FILING DATE July 20, 2005			

U.S. PATENT DOCUMENTS						
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS
	1	4,835,089	05/30/1989	Iwayanagi et al.		
	2	5,919,599	07/06/1999	Meador et al.		
	3	5,693,691	12/02/1997	Flaim et al.		
	4	6,057,239	05/02/2000	Wang et al.		

FOREIGN PATENT DOCUMENTS						
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS
	5	WO 02/05035 A1 w/abstract	01/17/2002	WIPO		
	6	EP 1 150 343 A2	10/31/2001	Europe		
	7	JP A 2001-83705 w/abstr. + trans.	03/30/2001	Japan		
	8	JP A 2002-47430 w/abstr. + trans.	02/12/2002	Japan		
	9	JP A 48-67447	09/14/1973	Japan		
	10	JP A 61-205494 w/abstract	09/11/1986	Japan		
	11	JP A 10-215893 w/abstr. + trans.	08/18/1998	Japan		

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)		
	12	Lynch et al., "Properties and Performance of Near UV Reflectivity Control Layers," SPIE Vol. 2195, pp. 225-229, 1994
	13	Taylor et al., "Methacrylate Resists and Antireflective Coatings for 193 nm Lithography," Part of the SPIE Conference on Advances in Resist Technology and Processing XVI, Vol. 3678, pp. 174-185, March 1999
	14	Meador et al., "Recent Progress in 193 nm Antireflective Coatings," Part of the SPIE Conference on Advances in Resist Technology and Processing XVI, Vol. 3678; pp. 800-809, March 1999

EXAMINER	DATE CONSIDERED
Examiner: Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	

Date: July 20, 2005